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L.M.J

Patent  
Attorney's Docket No. 018414-060

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of	)	Attention: <b>Drafting Branch</b>
Jang F. CHEN, et al.	)	Allowed: January 10, 1994
Application No.: 08/149,122	)	Batch: U09
Filed: November 3, 1993	)	Group Art Unit: 1503
For: METHOD FOR IMPROVED LITHO- GRAPHIC PATTERNING IN A SEMICONDUCTOR FABRICATION PROCESS	)	Examiner: T. MOSLEY

SUBMISSION OF FORMAL DRAWINGS

Box Issue Fee  
Honorable Commissioner of Patents and Trademarks  
Washington, D.C. 20231

**ATTN: OFFICIAL DRAFTSMAN**

Sir:

Enclosed please find 7 sheet(s) of formal drawings for review by the Patent and Trademark Office in connection with the Notice of Allowance mailed January 10, 1994. Should the enclosed drawings require changes, it is respectfully requested that the Patent and Trademark Office notify the undersigned attorney of same.

Respectfully submitted,

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Date: April 7, 1994

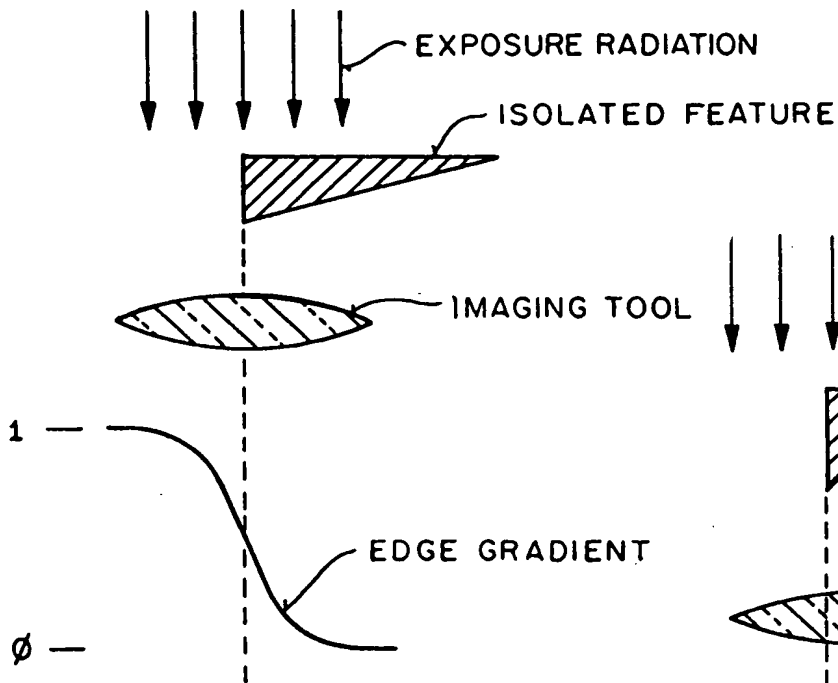


FIG. 1A

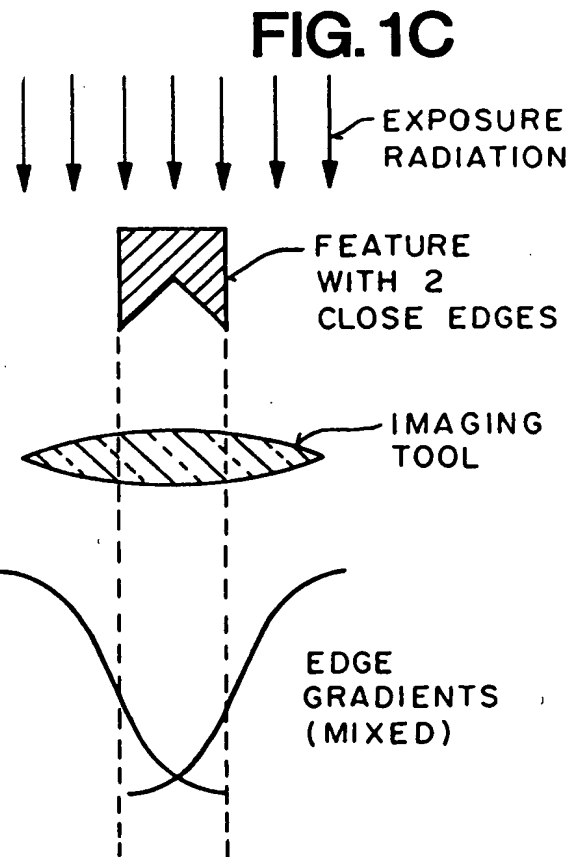


FIG. 1C

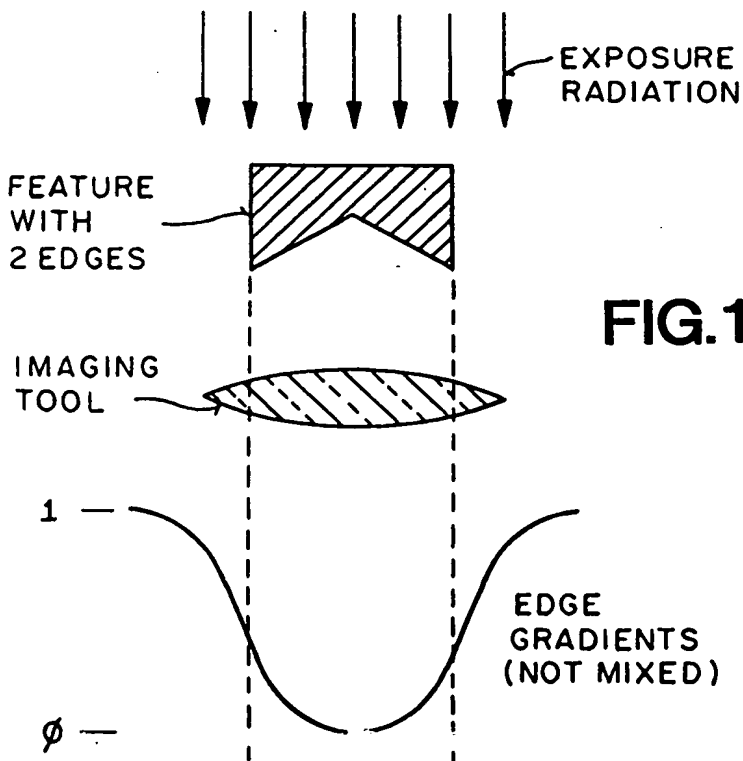
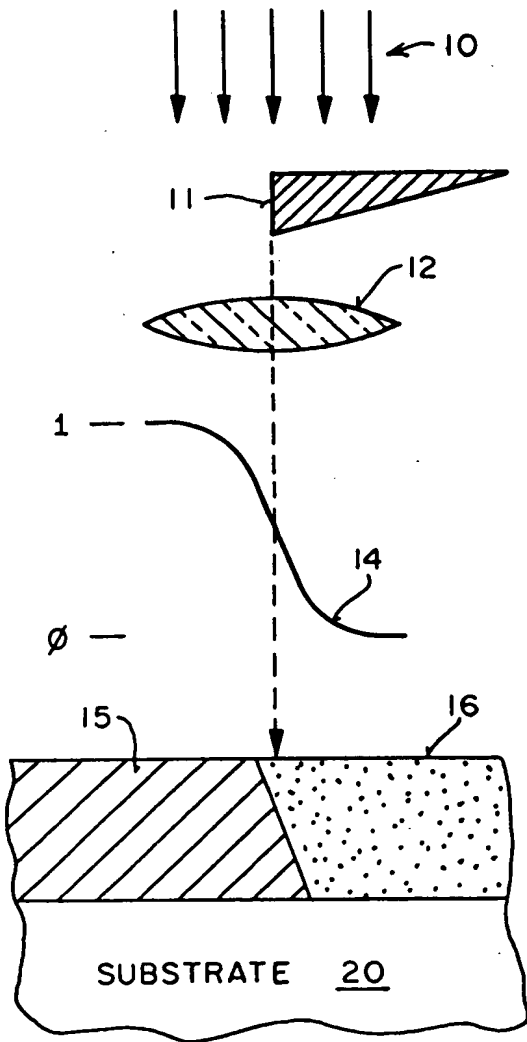
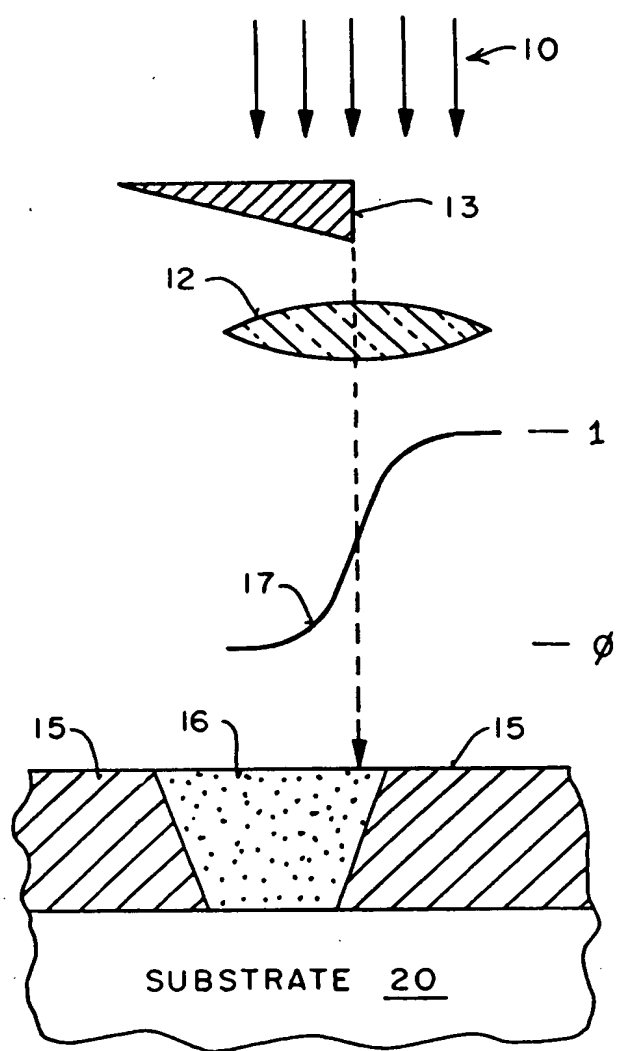


FIG. 1B

**FIG.2A**



**FIG.2B**



**FIG.2C**

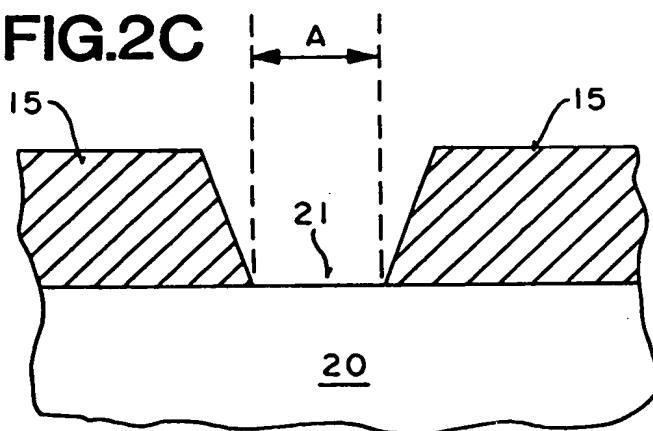
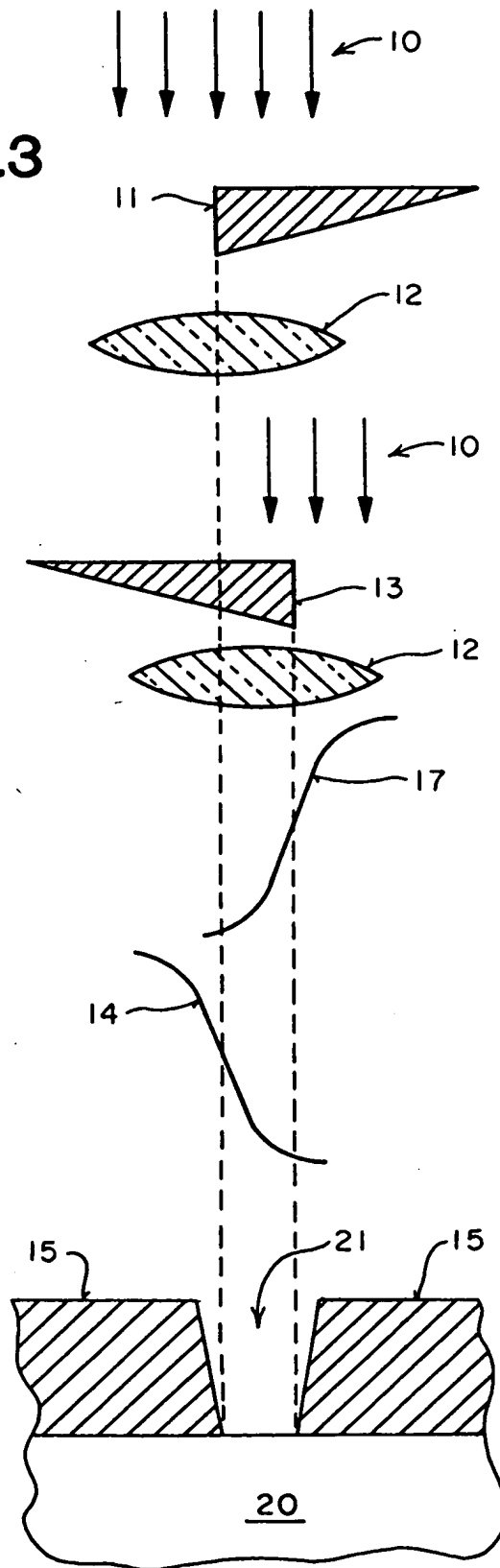
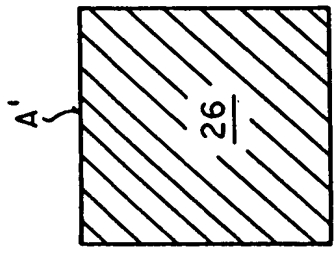
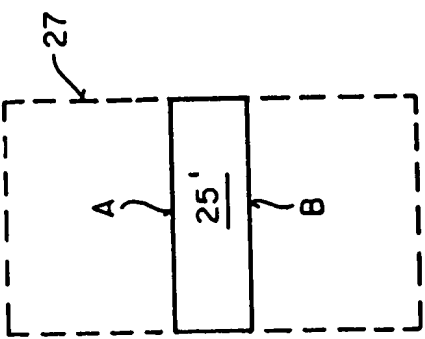
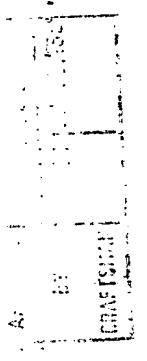
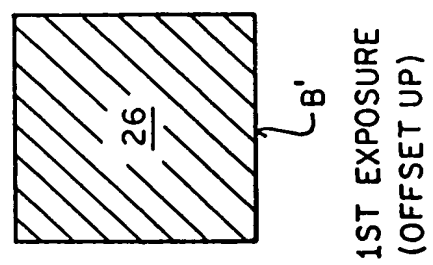


FIG.3





+



1ST EXPOSURE  
(OFFSET UP)

2ND EXPOSURE  
(OFFSET DOWN)

FIG.4

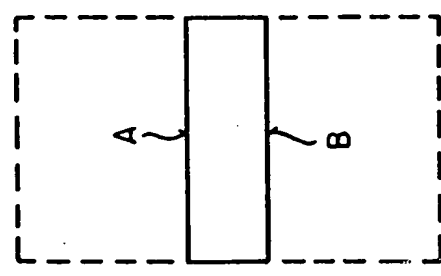
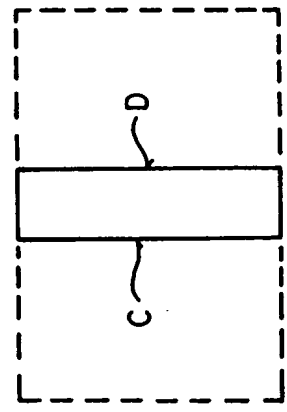
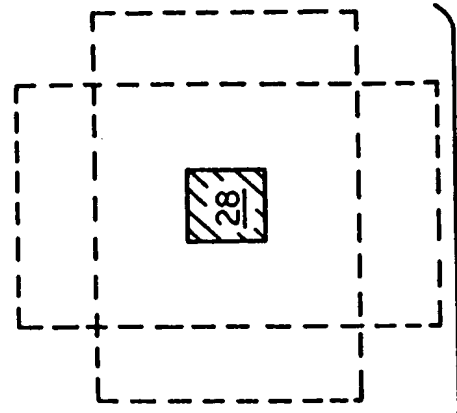
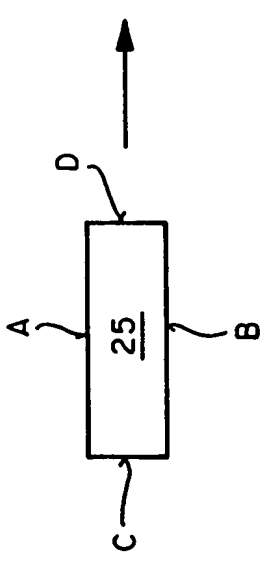
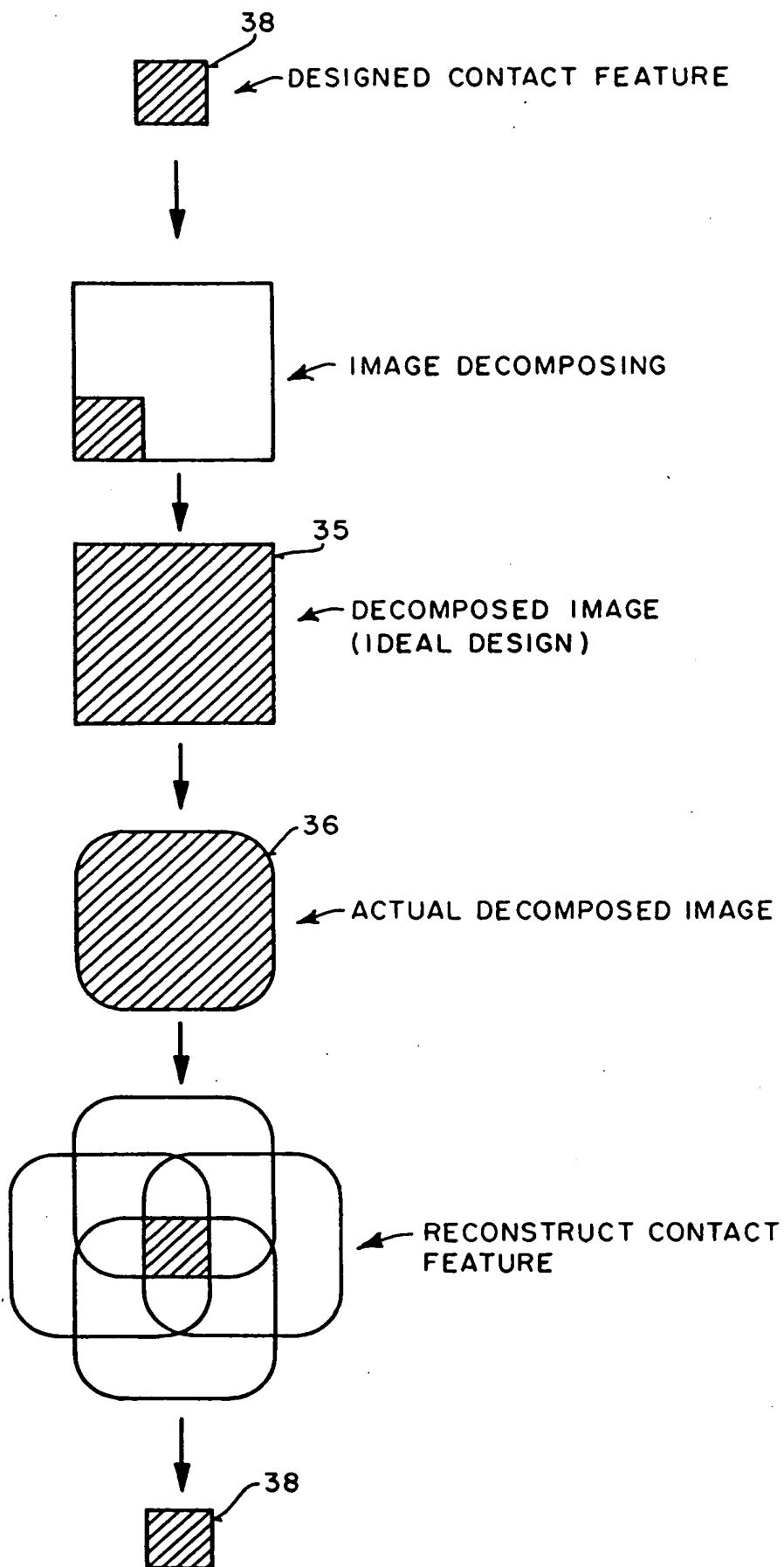
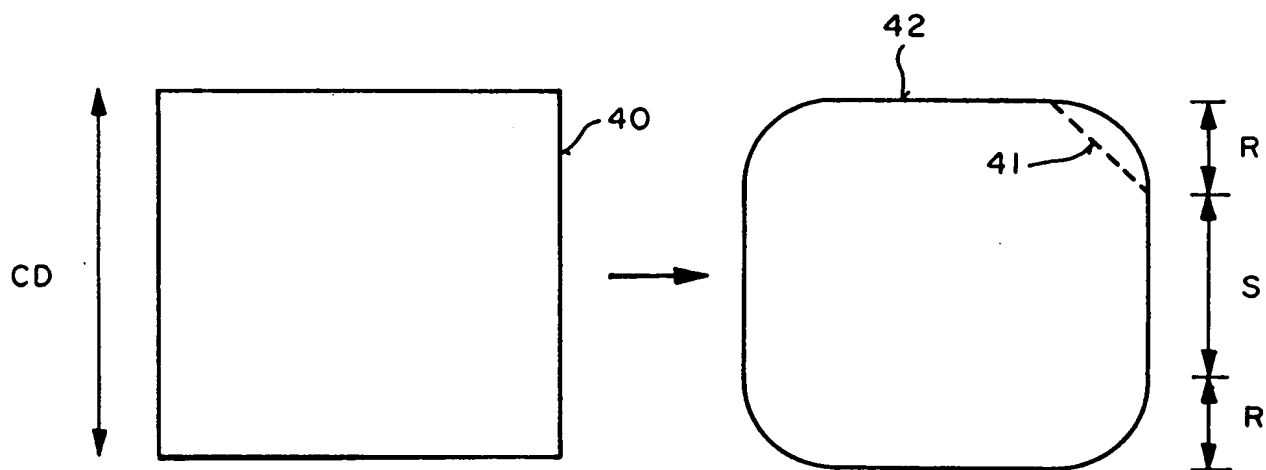


FIG.5

FIG.6

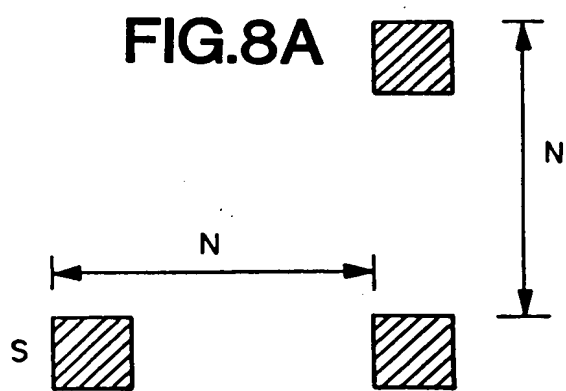




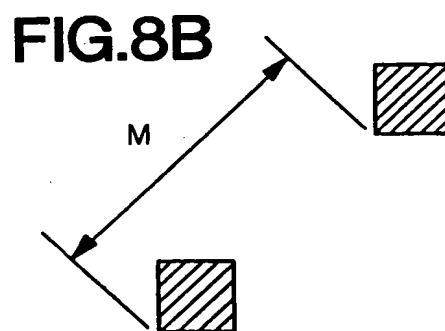
$$R = \frac{\lambda}{2 NA}$$

$$S = CD - \left( \frac{\lambda}{NA} \right)$$

**FIG.7**



$$N = S + \left( \frac{\lambda}{NA} \right)$$



$$M = \sqrt{2} \left( \frac{\lambda}{NA} \right)$$

FIG.9

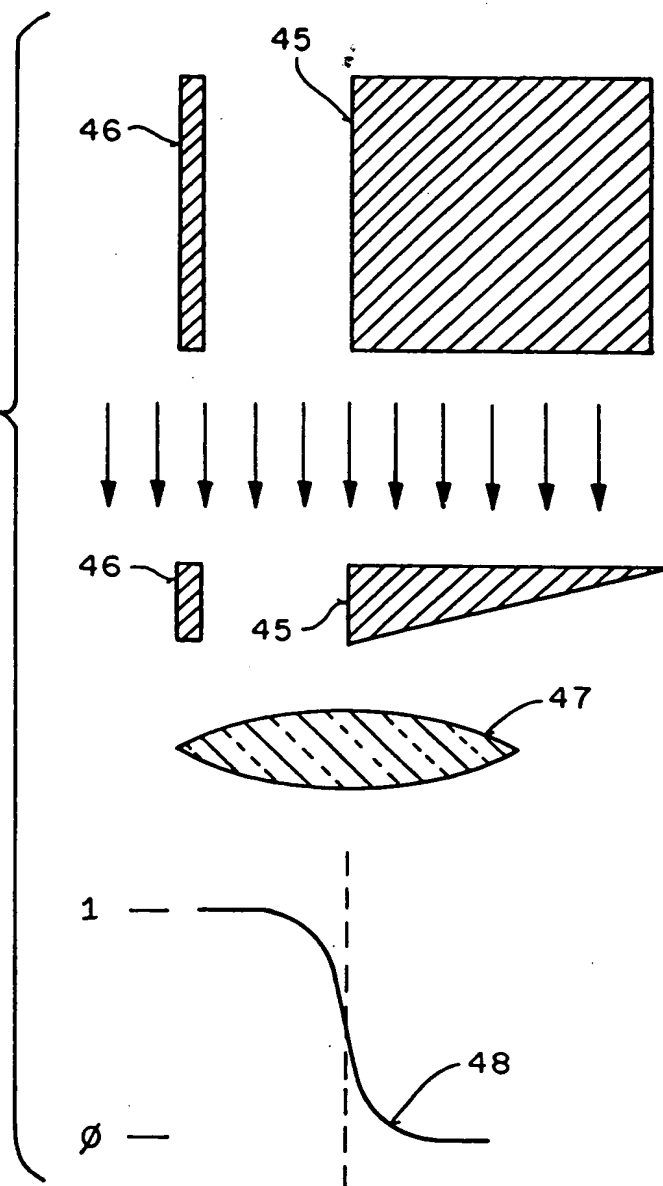


FIG.10

